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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609 considered. Include copy of this form with next communication to the applicant.	Draw line through citation if not in conformance and not

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Information Disclosure Citation in an Application						nit Filing Da	Filing Date June 27, 2003		
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				U.S. PATENT DOCUMENT	S				
		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE		
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				NON-PATENT DOCUMEN	TS				
	-	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)						DATE	
MA	R.	Edward Suttile et al.'s "Streamlining the front-end reticle fabrication process by improving mask ordering" at internet address http://www.micromagazine.com/archive/02/06/suttile.html and published in June 2002 Issue of Micro Magazine. 10 Pages June 2002						ne 2002	
нΑ	S.	Brock Hotaling, "MaskPilot Revolutionizes Semiconductor Software," Reticle and Mask Solutions, Vol. I, No. 1, Fall 2002, 4 Pages							
MA	т.	Photronics, Inc., "Photronics eBeam Phase Masks: Tackling the Challenges of Special Lightwave Applications," Reticle and Mask Solutions, Vol. XIII, No. 1, Spring 2002, 4 Pages							
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